

# ALD 2016 Ireland

**Dr Mike Cooke**  
**CTO – Plasma**  
**Oxford Instruments**



Mike Cooke leads technology development at Oxford Instruments Plasma Technology division, where he has developed induction coupled plasma sources, and a wide range of substrate tables covering cryogenic silicon etching through to 1200C deposition for graphene processing.

OIPT has introduced plasma-enhanced ALD, 450mm plasma etch and PECVD, and deep silicon etching during this time. Quote: 'The substrate is the best diagnostic'.